

Theoretical study of field emission from dielectric coated surfaces

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Introduction

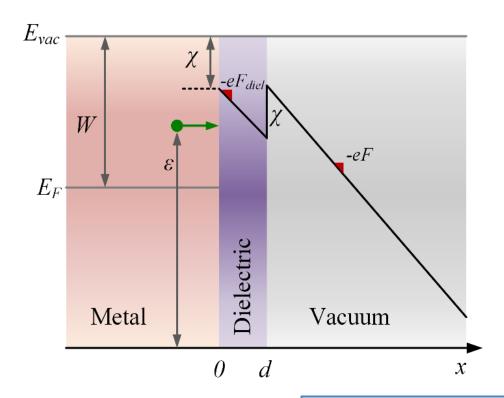
- Electron field emission plays an essential role in a wide range of applications, including
 - Electron microscopes
 - X-ray sources
 - High current cathodes
 - High power electromagnetic sources and amplifiers
 - Vacuum microelectronics
 - Emerging quantum nanoelectronics
- Field emitters attract intensive attention, because of
 - High efficiency
 - High brightness
 - Low emittance
 - Miniaturized device size



Field emitters with coating

- Artificial coating: Ultra-thin coatings are fabricated onto metallic cathodes to provide chemical and mechanical protection, and longer current stability, smaller turn-on electric field and enhanced current emission due to the lowering of the effective potential barrier [1], [2].
- Naturally formed coating: Native oxides or foreign adsorbates can be easily formed on the surface of the emitter at low vacuum condition [3].
- Coating on the cathode surface forms a double-layer potential barrier
 - Strongly influences the field emission current.
 - Has its potential to change the electrons' mean transverse energy behavior that affects beam quality, important to photoinjectors for future x-ray free electron lasers (XFELs) [4]
- [1] L. W. Swanson and R. W. Strayer, J. Chem. Phys., 48(6), 2421–2442 (1968).
- [2] X. Xiong et al., ACS Nano, 14(7), 8806–8815 (2020).
- [3] M. Morita and T. Ohmi, Jpn. J. Appl. Phys. 33, 370 (1994).
- [4] G. Wang, P. Yang, N. A. Moody, and E. R. Batista, npj 2D Mater Appl. 2, 17 (2018).





Potential barrier

$$V(x)$$

$$= \begin{cases} 0, & x < 0, \\ E_F + W - \chi - eF_{diel}x, & 0 \le x < d, \\ E_F + W + e(F - F_{diel})d - eFx, & x \ge d. \end{cases}$$

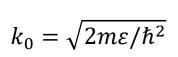
$$-\frac{\hbar^2}{2m}\frac{\partial^2}{\partial x^2}\psi(x) + [V(x) - \varepsilon]\psi(x) = 0$$

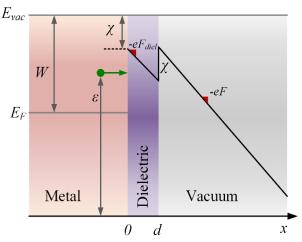
 $\psi(x)$: complex electron wave function



x < 0 (Inside metal)

$$\psi_I(x) = e^{ik_0x} + R_1 e^{-ik_0x}$$
Incident plane wave Reflected waves





$0 \le x < d$ (Inside dielectric)

$$\psi_{II}(x) = aAi(-\eta_1) + bBi(-\eta_1)$$

x ≥ d (Vacuum Region)

$$\psi_{III}(x) = T_3[Ai(-\eta_2) - iBi(-\eta_2)]$$

$$\eta_1 = \left(\frac{2meF_{diel}}{\hbar^2}\right)^{1/3} \left(x + \frac{\varepsilon - V_1}{eF_{diel}}\right)$$

$$V_1 = W + E_F - \chi$$

$$\eta_2 = \left(\frac{2meF}{\hbar^2}\right)^{1/3} \left(x + \frac{\varepsilon - V_2}{eF}\right)$$

$$V_2 = W + E_F + e(F - F_{diel})d$$



Boundary conditions at metal-dielectric interface & dielectric-vacuum interface

$$\begin{aligned} \psi_{I}(x=0) &= \psi_{II}(x=0) \\ \frac{\partial \psi_{I}}{\partial x} \Big|_{x=0} &= \frac{\partial \psi_{II}}{\partial x} \Big|_{x=0} \\ \psi_{II}(x=d) &= \psi_{III}(x=d) \\ \frac{\partial \psi_{II}}{\partial x} \Big|_{x=d} &= \frac{\partial \psi_{III}}{\partial x} \Big|_{x=d} \end{aligned}$$

Electron transmission probability

$$D(\varepsilon) = \frac{J_3(\varepsilon)}{J_i(\varepsilon)} \qquad \text{with} \quad J = \frac{i\hbar}{2m} (\psi \nabla \psi^* - \psi^* \nabla \psi)$$

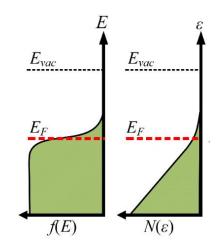
Electron transmission probability

$$D(\varepsilon) = \frac{1}{\pi} \frac{1}{k_0} \left(\frac{2meF}{\hbar^2}\right)^{1/3} |T_3|^2$$

Emission current density

$$J = e \int_0^\infty D(\varepsilon) N(\varepsilon) \ d\varepsilon$$

$$N(\varepsilon) = \frac{mk_BT}{2\pi^2\hbar^3} \ln\left[1 + \exp\left(\frac{E_F - \varepsilon}{k_BT}\right)\right]$$



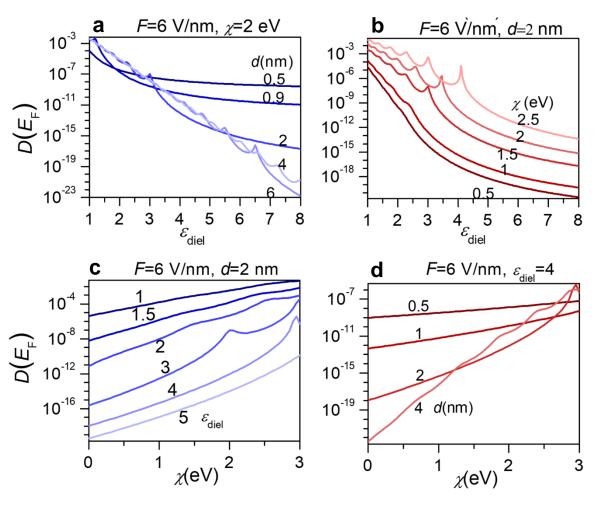
where $N(\varepsilon)d\varepsilon$ is the number density of electrons inside metal with longitudinal energy between ε and $\varepsilon+d\varepsilon$ impinging on the surface of metal per unit time [a].

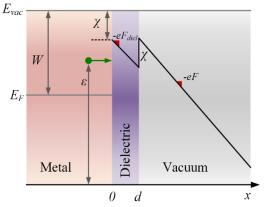
Y. Zhou and P. Zhang, "Theory of field emission from dielectric coated surfaces", Phys. Rev. Res., 2, 043439 (2020)

[a] K. L. Jensen, Introduction to the Physics of Electron Emission, 1 edition (Wiley, Hoboken, New Jersey, 2017).



The effects of dielectric properties on electron transmission probability



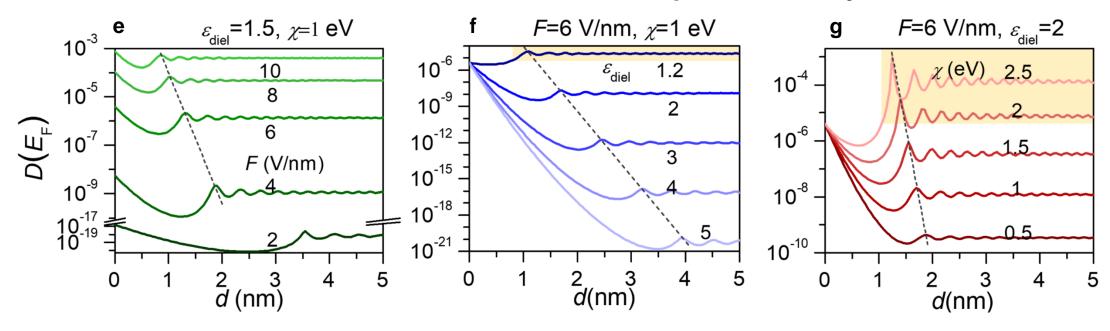


For 1D surface: $F_{
m diel} = F/arepsilon_{
m diel}$

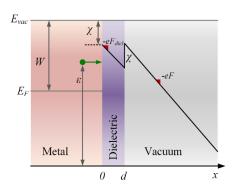
- ullet Electron transmission probability decreases with $arepsilon_{diel}$
- More resonances for emitters with thicker coating
- Stronger resonances for larger electron affinity
- Electron transmission probability increases with χ



The effects of dielectric properties on electron transmission probability

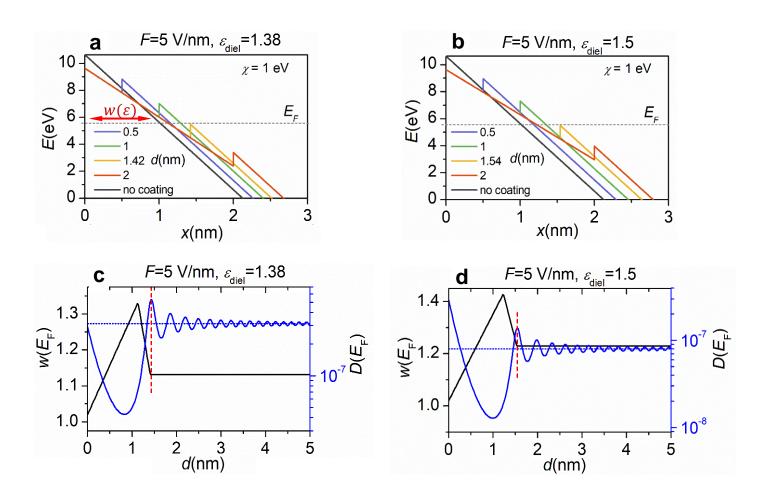


- Resonant peaks for $d > d_0 \approx \varepsilon_{diel} W/eF$
- Increasing F or χ shifts the maximum peak to smaller thickness
- Increasing ε_{diel} shifts the maximum peak to larger thickness
- Coated case can induce a transmission probability larger than the bare case





Potential profile and transmission probability



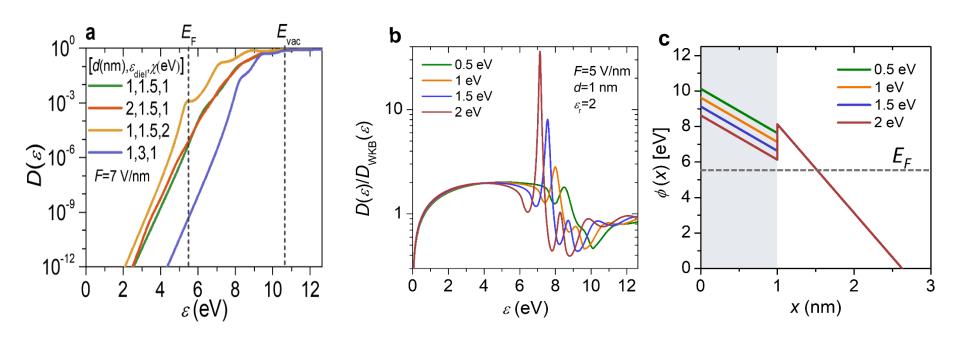
• The first resonance peak is at $d_0 \approx \varepsilon_{diel} W/eF$

• $D(E_F)$ oscillates around a constant, which is the tunneling probability through a single triangular barrier in thick dielectric.

Y. Zhou and P. Zhang, "Theory of field emission from dielectric coated surfaces", Phys. Rev. Res., 2, 043439 (2020)

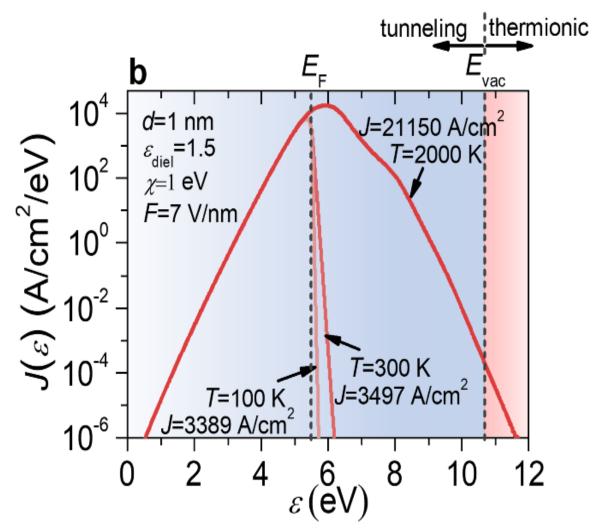


Potential profile and transmission probability



Stronger resonance is observed for larger electron affinity

Field emission and thermionic emission

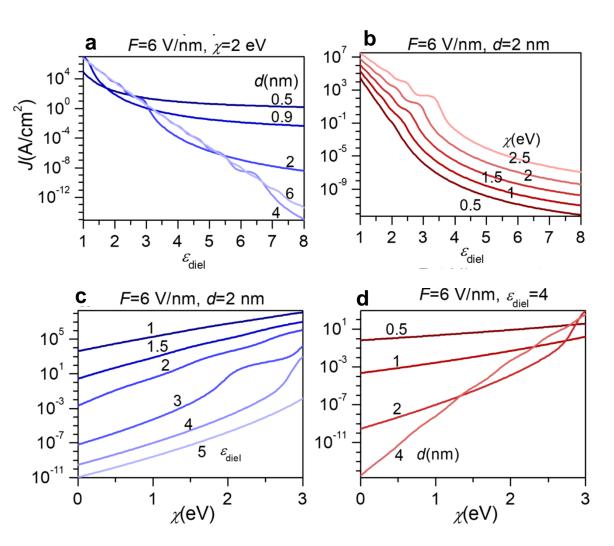


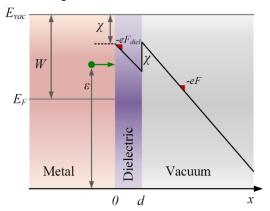
$$J(\varepsilon) = D(\varepsilon)N(\varepsilon)$$

$$N(\varepsilon) = \frac{mk_B T}{2\pi^2 \hbar^3} \ln \left[1 + \exp\left(\frac{E_F - \varepsilon}{k_B T}\right) \right]$$

 The model includes not only field emission but also thermionic emission

The effects of dielectric properties on field emission current density



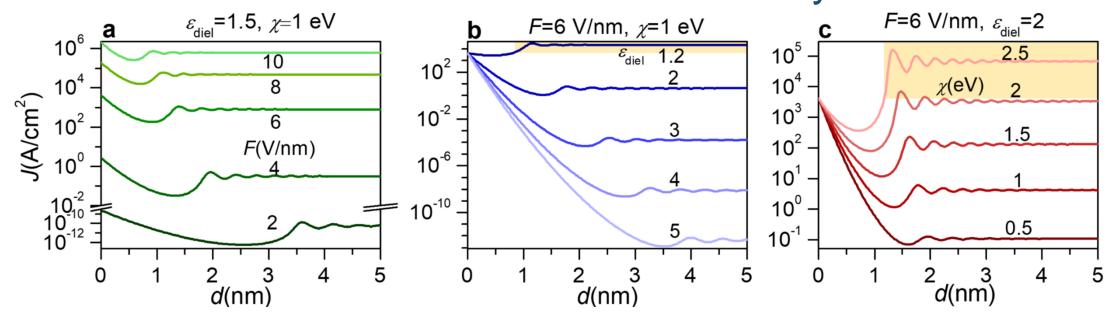


For 1D surface: $F_{
m diel} = F/arepsilon_{
m diel}$

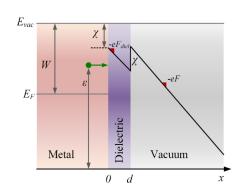
- J decreases with ε_{diel}
- Resonance peaks are not as sharp as in $D(E_F)$ vs ε_{diel}
- J increases with χ



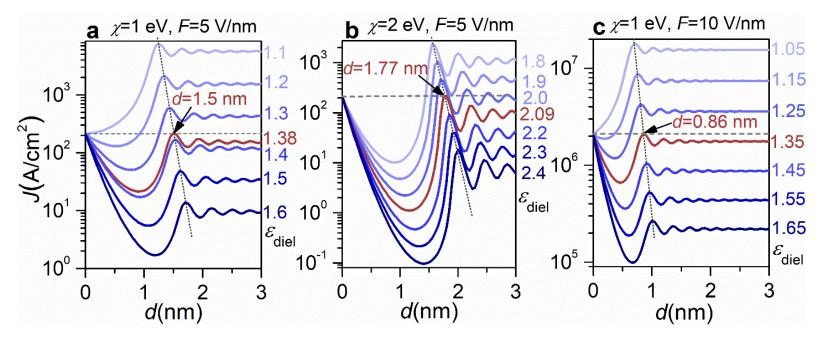
The effects of dielectric properties on field emission current density



- Resonant peaks for $d > d_0 \approx \varepsilon_{diel} W/eF$
- Increasing F or χ shifts the maximum peak to smaller thickness
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- Coated case can induce a current density larger than the bare case

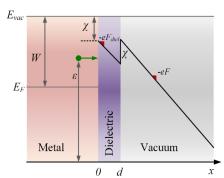


Determine the threshold thickness and threshold dielectric constant for current enhancement



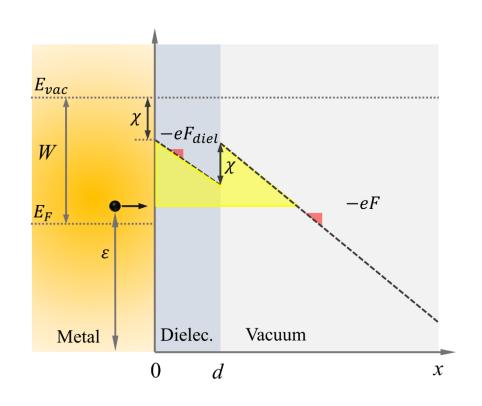
 An empirical relation between thickness threshold and dielectric constant threshold at room temperature:

$$d_{th}[nm] = \frac{\varepsilon_{diel}^{th}W}{eF}$$





Comparison with modified double-barrier Fowler-Nordheim equation [1-3]



- According to WKB approximation,
- Electron transmission probability
- Electron emission current density

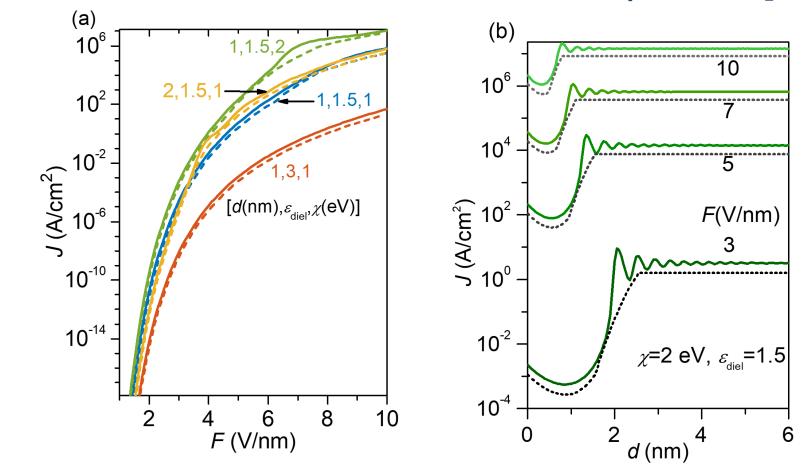
$$Q(\varepsilon) = 2 \int_0^{x_1} \sqrt{\frac{2m}{\hbar^2} [V(x) - \varepsilon]} dx$$

$$D(\varepsilon) = \exp[Q(\varepsilon)]$$

$$J = e \int_0^\infty D(\varepsilon) N(\varepsilon) \, d\varepsilon$$

- [1] Q.-A. Huang, J. Appl. Phys. 79(7), 3703-3707, (1996).
- [2] P. D. Keathley et al., Ann. Phys., 525(1-2), 144-150 (2013).
- [3] K. L. Jensen, et al., J. Appl. Phys. 127(23), 235301, (2020).

Comparison with modified double-barrier Fowler-Nordheim equation [1-3]



- Good agreement in the scaling
- Resonance behavior in J vs. d cannot be revealed by the modified FN equation

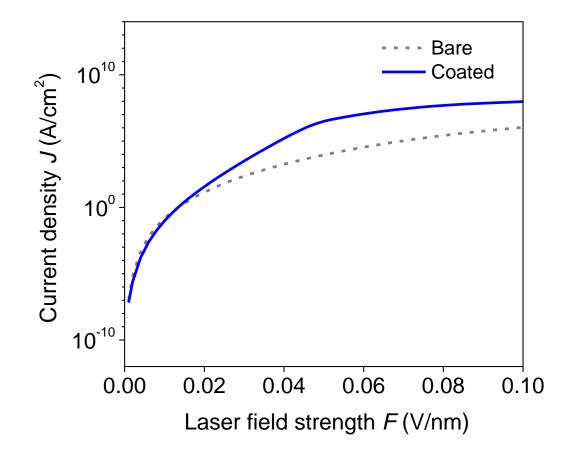
Thin dielectric coated plasmonic photoemitter

Plasmonic field confinement **Electron affinity x** Reduced tunneling barrier Enhanced fields at Au surface (a) $_{x10^{-18}}$ (c) (b) Vacuum at 590nm $oldsymbol{eta}_{\mathsf{Au}}$ **Bare** ка Bare **Plasmonic** $E_{ m Vac}$ 15 field decay 590 nm e⁻⊹ 25 Power absorption in Au (W) F (V/nm) 0.01 15 ---- 0.03 Au Au Distance to metal surface z (nm) $\boldsymbol{\beta}_{\mathsf{Au}}$ Coated Plasmonic field Coated Au Vacuum at 608nm 200 608 nm • confinement $E_{ m Vac}$ 100 5-Au F(V/nm) ·-·-0.03 --- 0.05 400 600 800 1000 Wavelength (nm)

Distance to metal surface z (nm)

X. Xiong, Y. Zhou, Y. Luo, X. Li, M. Bosman, L. K. Ang, P. Zhang, and L. Wu, "Plasmon-Enhanced Resonant Photoemission Using Atomically Thick Dielectric Coatings", ACS Nano, 14, 8806 - 8815 (2020). MICHIGAN STATE UNIVERSITY

Thin dielectric coated plasmonic photoemitter

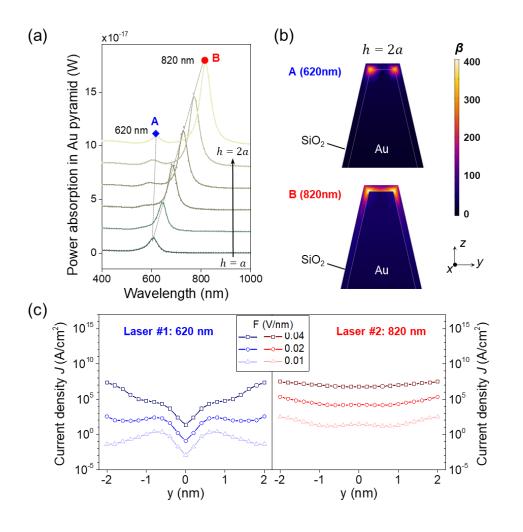


For F = 0.014 - 1 V/nm, J from the coated photoemitter is **enhanced by at least 2 orders of magnitude** as compared to the bare emitter.

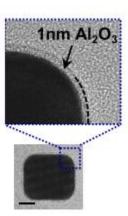
X. Xiong, Y. Zhou, Y. Luo, X. Li, M. Bosman, L. K. Ang, P. Zhang, and L. Wu, "Plasmon-Enhanced Resonant Photoemission Using Atomically Thick Dielectric Coatings", ACS Nano, 14, 8806 – 8815 (2020).



Thin dielectric coated plasmonic photoemitter



Tunable photoemission at different plasmonic resonant wavelengths



X. Xiong, Y. Zhou, Y. Luo, X. Li, M. Bosman, L. K. Ang, P. Zhang, and L. Wu, "Plasmon-Enhanced Resonant Photoemission Using Atomically Thick Dielectric Coatings", ACS Nano, 14, 8806 – 8815 (2020).



Summary

- An exact analytical quantum model is constructed for electron emission from dielectric coated surfaces.
- Cathodes with coatings of smaller dielectric constant and larger electron
 affinity tend to emit a larger current density than the bare metal surfaces.
- Empirical relation of the threshold thickness and threshold dielectric constant is proposed.
- The model shows good agreement in scaling with modified double-barrier Fowler-Nordheim equation, but also reveals new resonant peaks.
- Plasmon resonant photoemission from dielectric coated photoemitter is also studied.



NanoPATh Group

Nanoelectronics, Plasmas, & Accelerator Technology

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